

(19) World Intellectual Property Organization

International Bureau

(43) International publication date

1 August 2002 (01.08.2002)



PCT



G00002

(10) International publication number

WO 02/059069 A1

(51) International patent classification⁷:

C07C 39/16, 37/20

(21) International application number: PCT/FR02/00042

(22) International filing date: 8 January 2002 (08.01.2002)

(25) Language of filing: French

(26) Language of publication: French

(30) Data relating to the priority:

01/00,882 23 January 2001 (23.01.2001) FR

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La Défense (FR).(81) Designated states (national): AE, AG, AL, AM, AT, AU,
AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR,
CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE,
GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR,
KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK,
MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU,
SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA,
UG, US, UZ, VN, YU, ZA, ZM, ZW.(84) Designated states (regional): ARIPO Patent (GH, GM,
KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian
Patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),
European Patent (AT, BE, CH, CY, DE, DK, ES, FI, FR,
GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI Patent
(BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR,
NE, SN, TD, TG).

Declaration under Rule 4.17:

- as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZM, ZW, ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG)

- of inventorship (Rule 4.17(iv)) for the following designation US

Published:

- With the International Search Report.

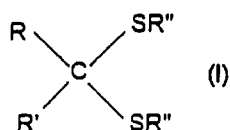
For an explanation of the two-letter codes and the other abbreviations, reference is made to the explanations ("Guidance Notes on Codes and Abbreviations") at the beginning of each regular edition of the PCT Gazette.

As printed

(54) Title: METHOD FOR MAKING BISPHENOL A

(54) Titre : PROCEDE DE FABRICATION DU BISPHENOL A

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(57) Abstract: The invention concerns a continuous method for making bisphenol A which consists in: reacting phenol and acetone in the presence of a strong acid catalyst and a co-catalyst; said method is carried out by using as co-catalyst a dithioether of general formula (I) wherein the symbols R and (R') represent each a hydrogen atom, an alkyl radical or a phenyl radical, and the symbol R'' represents an alkyl radical optionally substituted.

(57) Abrégé : Le procédé continu de fabrication du bisphénol A selon l'invention, par réaction du phénol et de l'acétone en présence d'un catalyseur acide fort et d'un co-catalyseur, est réalisé en utilisant comme co-catalyseur un dithioéther de formule générale (I) dans laquelle les symboles R et (R') représentent chacun un atome d'hydrogène, un radical alkyle ou un radical phényle, et le symbole R'' représente un radical alkyle éventuellement substitué



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